



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	<i>Baer et al.</i>)	Group No.:	1763
Serial No.:	10/675,697)	Examiner:	Arancibia
Filed:	09/30/2003)	Docket No.:	<i>HSJ9-2003-0032US1</i>

For: *"METHOD OF FORMING A READ SENSOR USING PHOTORESIST
STRUCTURES WITHOUT UNDERCUTS WHICH ARE REMOVED
USING CHEMICAL-MECHANICAL POLISHING (CMP) LIFT-OFF
PROCESSES"*

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

AMENDMENT AND REQUEST FOR RECONSIDERATION

For the contemporaneously submitted *Request for Continued Examination (RCE)* for the above-referenced patent application, the Applicant respectfully submits this Amendment and Request for Reconsideration for entry prior to substantive examination.